

What is claimed is:

1. A process for making a mask for use in a process for curing a photosensitive material, the process comprising steps of:
providing a thin transparent material of substantially uniform thickness;
forming a pattern of opaque regions in the material according to a predetermined first pattern; and
embossing the material according to a predetermined second pattern.
2. The process according to Claim 1, wherein the first pattern substantially correlates with the second pattern to form a combined non-random repeating pattern.
3. The process according to Claim 1, wherein the steps of forming the opaque regions and embossing the material are performed simultaneously.
4. The process according to Claim 1, wherein the step of forming a pattern of opaque regions comprises applying ink to selected regions of the transparent material.
5. The process according to Claim 4, wherein the selected regions comprise distal surfaces of the embossed areas of the material.
6. The process according to Claim 1, wherein the step of providing a thin transparent material comprises providing a transparent film.
7. The process according to Claim 1, wherein the step of forming a pattern of opaque regions comprises forming opaque regions having differential opacities.

8. The process according to Claim 1, wherein the step of forming a pattern of opaque regions comprises forming opaque regions having gradient opacity gradually changing in at least one direction.